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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Yasuo KOBAYASHI, et al.

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U.S. Serial No.: To Be Assigned

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Filed: : Herewith

Examiner: To Be Assigned

For: SEMICONDUCTOR DEVICE, MANUFACTURING METHOD OF  
SEMICONDUCTOR DEVICE, AND GAS FOR PLASMA CVD PROCESS

PRELIMINARY AMENDMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Prior to or concurrent with calculation of the filing fees, please amend this application as follows.